

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Ibrahim Abdulhalim, et al.
Title: Periodic Patterns And Technique To Control Misalignment Between Two Layers
Application No.: 09/833,084 Filing Date: April 10, 2001
Examiner: Zandra V. Smith Group Art Unit: 1775
Docket No.: TNCR.196US0 Conf. No.: 8866

Certificate of Mailing Under 37 CFR 1.8

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Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.

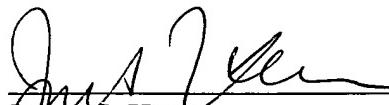
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Attorney Docket No.:
TNCR.196US0

Application No.:
09/833,084

This information disclosure statement is submitted under 37 C.F.R. § 1.97(b) and consequently no fee should be required. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

Respectfully submitted,



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U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>MAR 05 2004</i> <i>PATENT & TRADEMARK OFFICE</i>		Atty. Docket No. TNCR.196US0	Application No. 09/833,084
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	63	2002/00072001	Jun. 13, 2002	Brown et al.			
	64	2003/0002043	Jan. 2, 2003	Abdulhalim et al.			
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Examiner		Date Considered	
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>			